



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Ebrahim Andideh et al.

Serial No.: 10/712,205

Filed: November 12, 2003

For: Parallel Electrode Memory

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Art Unit: 2811

Examiner: Samuel A. Gebremariam

Art Docket: ITL1008US  
P15533

Assignee: Intel Corporation

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**DECLARATION OF PRIOR INVENTORSHIP**

Sir:

We the undersigned inventors hereby declare as follows:

1. We are the inventors of U.S. Patent Application 10/712,205.
2. On or before the filing date of April 2, 2002 of the United States published patent application 2003/0185048, we invented the subject matter of the above-referenced patent application and were diligent to filing a patent application thereon.
3. Namely, on or about January, 2002, we submitted an invention disclosure to obtain a patent application and a true and correct copy of that disclosure is attached hereto.
4. Referring to our claim 1, a first and second layer of memory material spaced from one another in a first direction is shown in that disclosure in Figure 1. There, there are successive polymer layers, polymer 1, polymer 2, polymer 3, all the way up to polymer n, spaced from one another in a first direction which is a vertical direction. Further, the claim calls for in a second address line substantially in said first direction through the first and second layers. The address line is labeled metal 1 in Figure 1.

Therefore, we clearly had conceived of the idea prior to the filing date of the cited reference.

5. We hereby declare that all statements made herein of our own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Date:

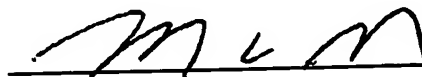
3/27/06



Ebrahim Andideh

Date:

3/22/06



Richard L. Coulson

**BOXCAR RELATED – SEND to WIRELESS COMMITTEE**  
**TMG INVENTION DISCLOSURE, Rev 1, 2/98**  
**Located at: <http://legal.intel.com>**

24237  
P15533

LEGAL ID# \_\_\_\_\_ (legal dept. use only)

DATE: Jan. 3, 2002

It is important to provide accurate and detailed information on this form (fill in ALL areas under Inventor[s]). The information will be used to evaluate your invention for possible filing as a patent application. When completed, please return this form to **Janice Boulden, Intel Legal Department at JF3-147. You can submit electronically if all of the information is electronic, including drawings and supervisor approval.** If you have any questions regarding this form or to whom it should be forwarded, please call **503-264-0444**.

Fill out the below and follow the instructions:

1. **Field of the Invention:**
- ☐ Semiconductor Process: device and integration
  - ☒ Semiconductor Process + Equipment: thin films
  - ☐ Semiconductor Process + Equipment: etch/litho
  - ☐ Circuit Design
  - ☐ Flash
  - ☐ Test
  - ☐ CQN (Q&R)
  - ☐ Packaging
  - ☐ Boards/Cartridge
  - ☐ Automation
  - ☐ Other

2. **Concise Title of Invention:**

A Novel Ferroelectric Polymer Memory Structure

3. **Brief Description of Invention (please use only space provided and font #10 or larger. Write the Key Elements of the Invention):**

***The invention is :***

Fabrication of horizontal polymer memory cell as shown in Figure 1.

#### 4. Inventor(s):

|   |                                     |  |                            |             |
|---|-------------------------------------|--|----------------------------|-------------|
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| Citizenship:<br>USA   | Supervisor Name:<br>Chi-Hwa Tsang   | Supervisor Phone:<br>613-7036                              | Supervisor M/S:<br>RA1-234 |             |
| Group Name: <u>TMG</u><br>Division Name: ATD____<br>PTD__X__CTM__CR__ | BUM Presenter:<br>Sanjay Panditji   | Inventor Signature:  |                            |             |
| <b>Inventor</b><br>Name: Rick Coulson                                 |                                     | SS# 522-98-7127  | Empl.# 10034900            | M/S:JF2-53  |
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| Citizenship:<br>USA   | Supervisor Name:<br>Sanjay Panditji | Supervisor Phone:<br>264-6675                              | Supervisor M/S:<br>JF2-53  |             |
| Group Name: <u>TMG</u><br>Division Name: ATD____<br>PTD__CTM__CR__    | BUM Presenter:<br>Sanjay Panditji   | Inventor Signature:  |                            |             |

5. **HAVE YOUR SUPERVISOR READ, DATE AND SIGN COMPLETED FORM (use first inventor's supervisor if multiple inventors)**

DATE: Jan . 2002

**BY THIS SIGNING, I (SUPERVISOR) ACKNOWLEDGE THAT I HAVE READ AND UNDERSTAND THIS DISCLOSURE, AND RECOMMEND THAT THE HONORARIUM BE PAID.**

6. **Has subject matter of present disclosure been disclosed or will it be disclosed outside Intel?**  
If yes, explain and give date: No  
(Give expected tape out date if applicable):
7. **Has the subject matter of present disclosure been published or will it be published outside of Intel? NO**  
If yes, explain and give date:
8. **Has a product using or manufactured using the present disclosure been sold or offered for sale?**  
If yes, explain and give date: NO
9. **Has this invention been conceived, or constructed during accomplishment of a government or third party contract? If yes, give contract name and number: NO**
10. **Explain the problem being addressed by the invention:**  
*This invention addresses the problem of:*  
Fabrication of smaller memory cell to increase the memory density as shown in Figure 1.
11. **Explain current state of the art (i.e., how the problem is solved today):**  
*Presently the problem described above is solved by*  
Memory cells are stacked and metal electrodes are located on top and bottom of the polymer memory cells.

**State of the Art**

Shown in Figure 2, lower density with more complicated integration processes.

**This invention**

Shown in Figure 1, higher density, lower fabrication cost.

12. **Explain technical advantages of the invention over current state of the art:**  
*The technical advantage of this invention is:*

This is a new approach for fabricating polymer memory

13. a. **Is the invention experimentally verified?** No  
b. **Is the invention verified with simulation?** N/A  
c. **If neither a. or b. above, then you can get a patent on the concept, but please explain the technical basis to justify that your invention will work (use extra space if necessary):**

14. **Detailed Description of Invention** (try to use only the space provided with font #10 or larger type. Refer to your drawings):  
Please see Figure 1.

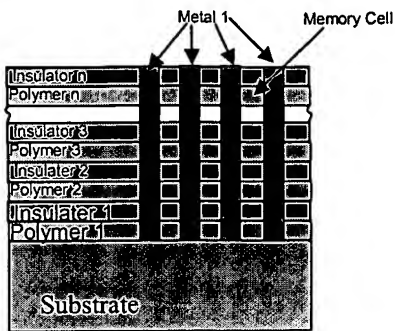


Figure 1. Each metal filled trench is a word line or a bit line.

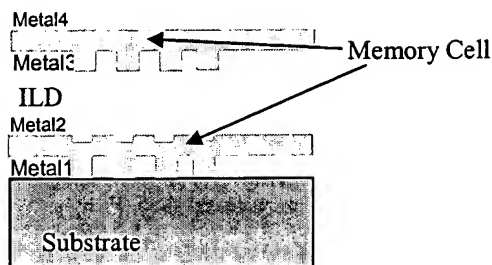


Figure 2. State of the art polymer memory structure.

15. **Referenced sketches/dwg's/diagrams:** (use additional page(s))
16. **Key Supporting Data (1 page limit on separate page):**  
This is a Conceptual Invention. We have not fabricated this structure yet.
17. **What is the product or process invention to be used on?** (e.g., P8xx, name of product, etc.):  
P822 and future polymer material integration.
18. **Have you reviewed your invention with a TMG Patent Mentor?** (see below for mentor names) If so, give name: